

Title (en)

Protected vapor-deposited metal layers.

Title (de)

Geschützte, im Vakuum aufgedampfte Metallschichten.

Title (fr)

Couches métalliques protégées obtenues par vaporisation sous vide.

Publication

EP 0087309 A1 19830831 (EN)

Application

EP 83300897 A 19830221

Priority

- US 35043782 A 19820222
- US 35072282 A 19820222
- US 35072482 A 19820222

Abstract (en)

A process for improving the abrasion resistance of vapor deposited metal layers which comprises vapor depositing a metal layer on at least one surface of a substrate and, before subjecting the metal layer to physical treatment or contact which would abrade the metal layer, vapor depositing onto said metal layer 1) a 1 to 600 nm layer of organic material having a vapor pressure at 20 DEG C equal to or less than that of 1-n-octanol said material having a) a carbonyl group not part of a carboxyl group, b) a phenoxy group, c) an ester group, or d) an alcohol group, or 2) a layer of organic material having a thickness of at least 1 nm and less than 30 nm and a) a carboxyl group, b) a saccharide, c) Rhodamine B, or d) phthalocyanine. The organic materials can improve the properties of the metal layer when used in photoresist imaging films.

IPC 1-7

C23C 13/04; **C23C 13/02**; **B05D 1/36**

IPC 8 full level

B05D 7/24 (2006.01); **C23C 14/56** (2006.01); **G03F 1/68** (2012.01)

CPC (source: EP)

B05D 1/60 (2013.01); **C23C 14/562** (2013.01); **G03F 1/48** (2013.01)

Citation (search report)

US 4268541 A 19810519 - IKEDA TOMOAKI, et al

Cited by

FR2712586A1; GB2247013A; GB2251434A; GB2247013B; GB2251434B; US6605317B1; US6565995B1; US7183008B1; WO0032719A1; US7303824B2; US6524727B1; US7235311B2; US6717354B1; US7354661B2; US7211334B2; WO9010611A1; WO9010724A1

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EP 0176693 A2 19860409; **EP 0176693 A3 19880413**; AU 1168783 A 19830901; BR 8300826 A 19831116; DE 3375029 D1 19880204; EP 0087309 A1 19830831; EP 0087309 B1 19871223; GR 77811 B 19840925

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EP 85109628 A 19830221; AU 1168783 A 19830221; BR 8300826 A 19830221; DE 3375029 T 19830221; EP 83300897 A 19830221; GR 830170554 A 19830321